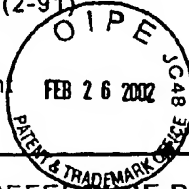


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List of Patents and Publications  
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### REFERENCE DESIGNATION

Ex'r	U.S. Patent Documents	Sub
Init	Document No.   Date   Name	Class   Class   File Date (when applicable)

IAA  
IAB

Ex'r	Foreign Patent Documents	Sub	Translation?
Init	Document No.   Date   Name	Class   Class	Yes   No

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